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33rd International Microprocesses and Nanotechnology Conference
MNC2020
Nov. 9-12, 2020

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- 1-1: Advanced Lithography and Patterning
- 1-2: Electron and Ion Beam Technologies
- 1-3: Patterning Materials
- 2-1: Nanocarbon & 2D Materials
- 2-2: Nanodevices
- 2-3: Nanofabrication
- 2-4: Inorganic Nanomaterials
- 2-5: Organic Nanomaterials
- 2-6: NanoTool
- 3: Nanoimprint, Hybrid-NIL, Biomimetics, and Functional Surfaces
- 4: BioMEMS, Lab on a Chip, and Nanobiotechnology
- 5: Microsystem Technology and MEMS
- 6: Atomic Layer Processing (ALP)

1-1: Advanced Lithography and Patterning

1-1: Advanced Lithography and Patterning Video distribution

1-1-1: Special Talk

Full Chip Curvilinear ILT with both Multi-Beam and VSB Mask Writers That Improves Wafer Process Windows by 2X (Special Talk)

Linyong (Leo) Pang 1, Ezequiel Vidal Russell 2, Bill Baggenstoss 2, Yang Lu 2, Michael Lee 2, Jennefir Digaum 2, Ming-Chuan Yang 2, Ryan Pearman 1, P.Jeffrey Ungar 1, Lu Sha 1, Ali Bouaricha 1, Michael Pomerantsev 1, Mariusz Niewczas 1, Kechang Wang 1, Bo Su 1, Michael Meyer 1, Aki Fujimura 1, 1 D2S and 2 Micron Technol., USA

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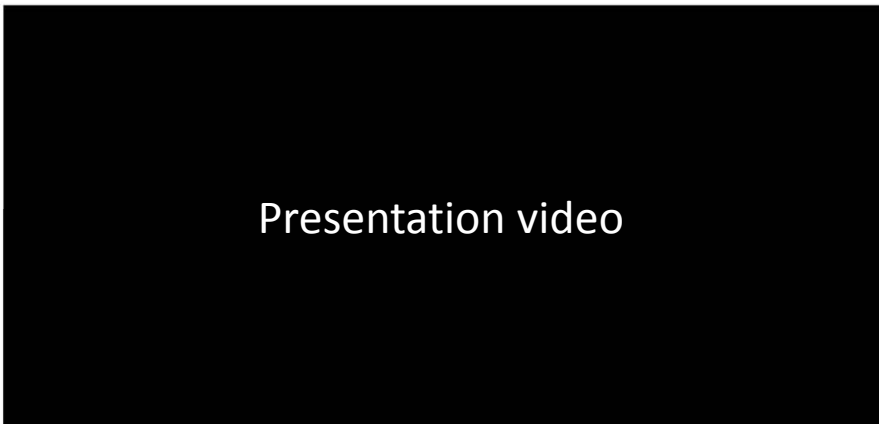
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Title: [Full Chip Curvilinear ILT with both Multi-Beam and VSB Mask Writers That Improves Wafer Process Windows by 2X \(Special Talk\)](#)




Speaker: **Linyong (Leo) Pang 1**, Ezequiel Vidal Russell 2, Bill Baggenstoss 2, Yang Lu 2, Michael Lee 2, Jennefir Digaum 2, Ming-Chuan Yang 2, Ryan Pearman 1, P.Jeffrey Ungar 1, Lu Sha 1, Ali Bouaricha 1, Michael Pomerantsev 1, Mariusz Niewczas 1, Kechang Wang 1, Bo Su 1, Michael Meyer 1, Aki Fujimura 1, 1 D2S and 2 Micron Technol., USA

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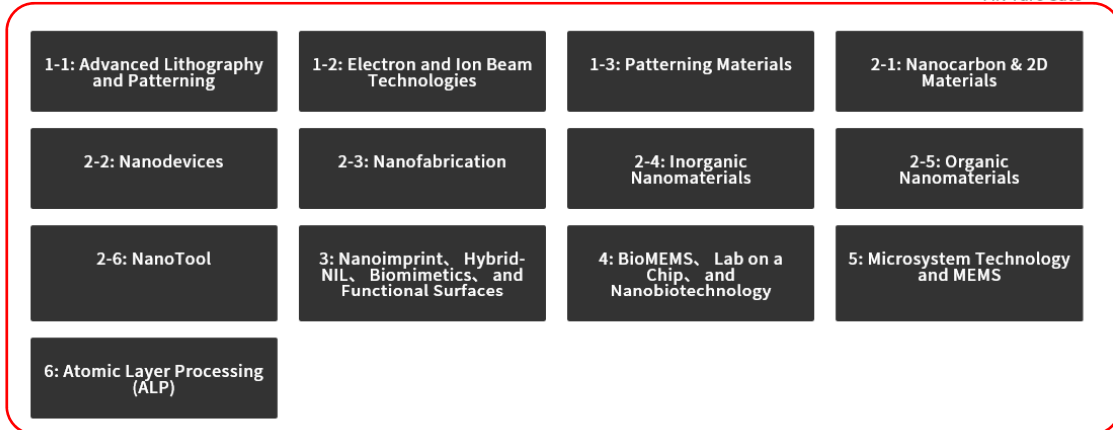


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